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(54) WAFER INSPECTION APPARATUS

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(57) Abstract:

PROBLEM TO BE SOLVED: To provide a wafer inspection apparatus which enables simplification of structure and reduction in time for the inspection process by adding a macroscopic inspection function to a wafer positioning section.

SOLUTION: This apparatus includes a microscopic inspection section 12 for performing microscopic observation of a wafer 2 selectively supplied from a carrier 1, and a wafer positioning section for vacuum checking the wafer 2 to a rotary table 70 by vacuum suction to rotate the wafer 2 and then detecting a positioning cut-out portion formed on the peripheral edge of the wafer 2 so as to position the wafer. The rotary table 70 has a rotation axis which moves up and down. The rotation axis may be inclined to swing in an arbitrary direction by a joy stick 24. Thus, with the same rotary table 70, the wafer 2 is positioned or inclined to swing by the joy stick 24 so as to perform microscopic observation.

